

Title (en)
DEVICE AND METHOD FOR HANDLING PROCESS GASES IN A PLASMA STIMULATED BY HIGH FREQUENCY ELECTROMAGNETIC WAVES

Title (de)
VORRICHTUNG UND VERFAHREN ZUR BEHANDLUNG VON PROZESSGASEN IN EINEM PLASMA ANGEREGT DURCH ELEKTROMAGNETISCHE WELLEN HOHER FREQUENZ

Title (fr)
DISPOSITIF ET PROCÉDÉ POUR TRAITER DES GAZ DE TRAITEMENT DANS UN PLASMA EXCITÉ PAR DES ONDES ÉLECTROMAGNÉTIQUES À HAUTE FRÉQUENCE

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Application
EP 14744363 A 20140729

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Abstract (en)
[origin: WO2015014839A1] The invention relates to a device for handling process gases in a plasma stimulated by electromagnetic waves, comprising a plasma chamber, which is lined by a dielectric, a generator for generating the electromagnetic waves and a waveguide assembly for feeding the electromagnetic waves into the plasma chamber, wherein the waveguide assembly has at least two feed points, each having an electric field waveguide branch, for feeding the electromagnetic waves as continuous waves into the dielectric.

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Citation (search report)
See references of WO 2015014839A1

Cited by
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